

## **Supplement Materials**

### **Novel Strategy to Prepare Pure Cu<sub>4</sub>TiSe<sub>4</sub> and Its High-Pressure Raman and Thermoelectric Performance Investigation**

Guangfeng Zhang <sup>a</sup>, Tonghan Yang <sup>b</sup>, Wei He <sup>a,\*</sup>, Zhikai Zhu <sup>c</sup>, Hui Luo <sup>a</sup>, Shuohai Fang <sup>a</sup>, Changzhong Liao <sup>a,\*</sup>

<sup>a</sup> State Key Laboratory of Featured Metal Materials and Life-cycle Safety for Composite Structures, MOE Key Laboratory of New Processing Technology for Nonferrous Metals and Materials, School of Resources, Environment and Materials, Guangxi University, Nanning 530004, China

<sup>b</sup> Guangxi Key Laboratory of Advanced Structural Materials and Carbon Neutralization, School of Materials and Environment, Guangxi Minzu University, Nanning 530105, China

<sup>c</sup> Center for High Pressure Science and Technology Advanced Research (HPSTAR), Shanghai 201203, China

\*Corresponding author:

Dr. Changzhong Liao, E-mail: [liaocz29@connect.hku.hk](mailto:liaocz29@connect.hku.hk)

Professor Wei He, E-mail: [wei\\_he@gxu.edu.cn](mailto:wei_he@gxu.edu.cn)

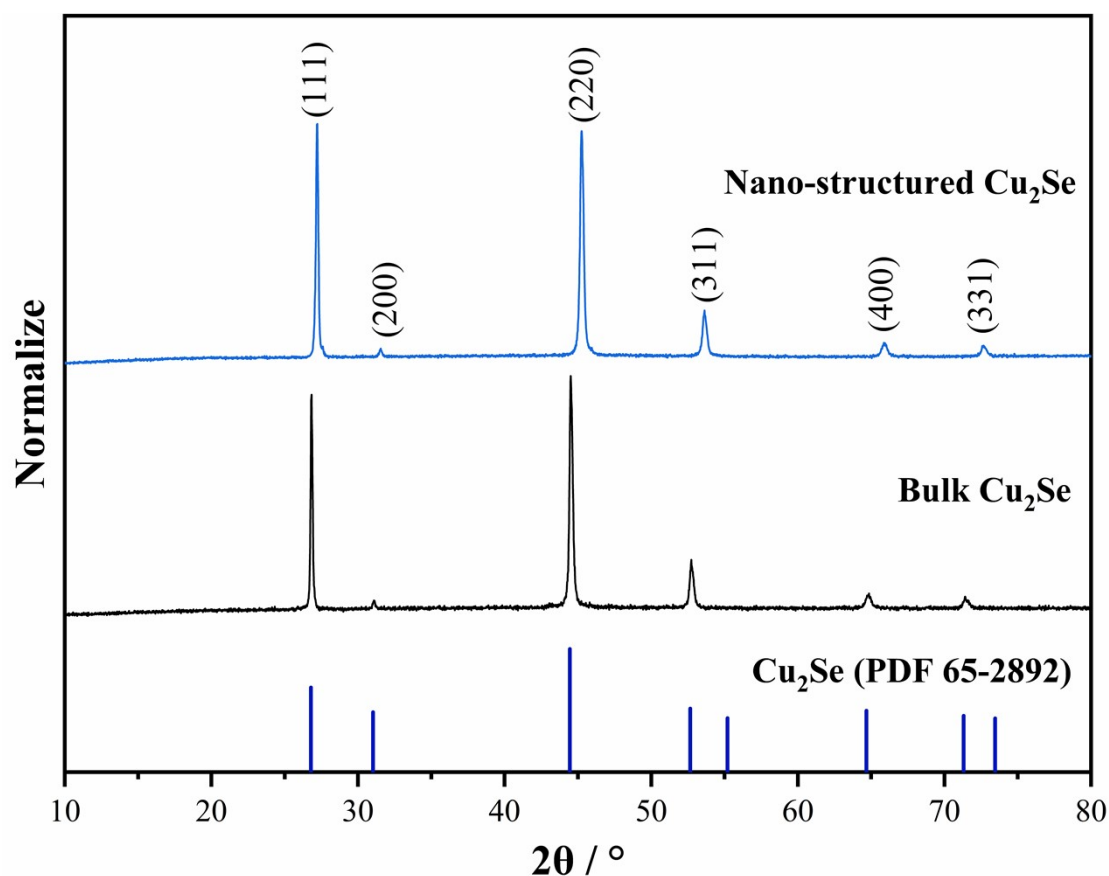


Figure S1 XRD patterns of  $\text{Cu}_2\text{Se}$  after different treatments in comparison with the standard card.

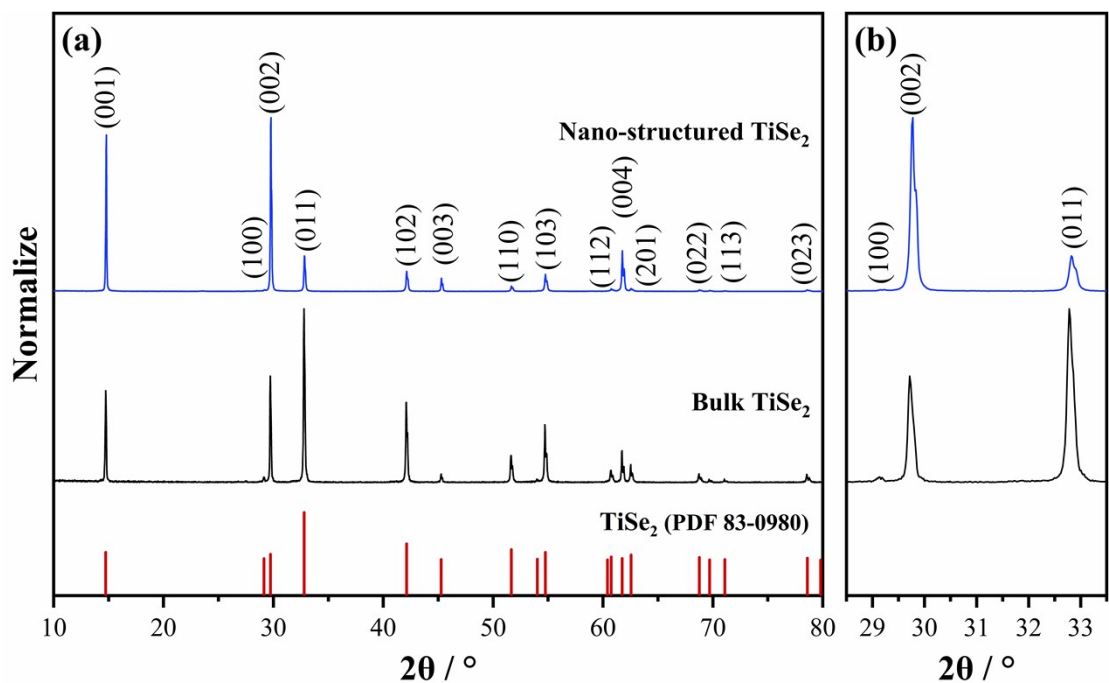


Figure S2 (a) XRD patterns of  $\text{TiSe}_2$  under different treatments in comparison with the standard card. (b) Amplified X-ray diffraction patterns at  $2\theta = 28\text{--}34^\circ$

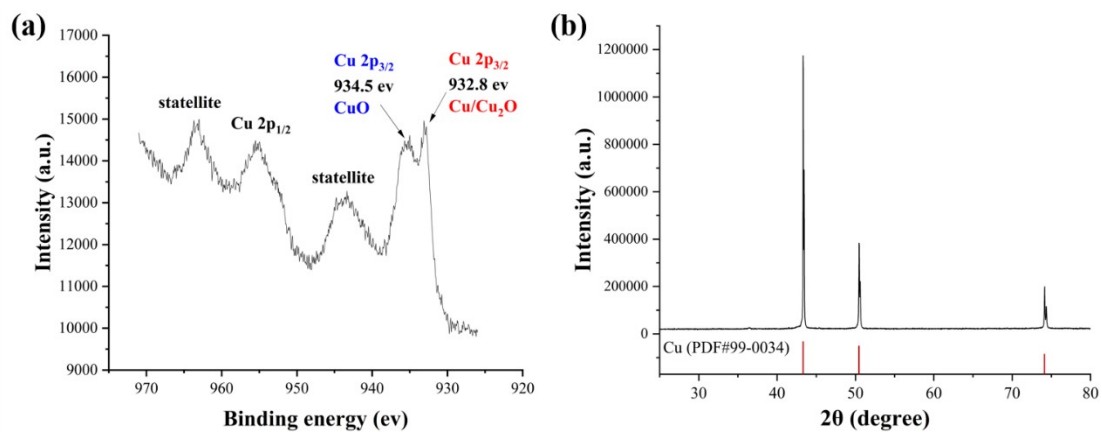


Figure S3 (a) The XPS pattern of Cu powder, (b) XRD pattern of Cu powder.

Table S1 The density of Bulk and Nano-structured Cu<sub>4</sub>TiSe<sub>4</sub> calculated by Archimedes' method.

Sample	Density (g/cm <sup>3</sup> )	Theoretical density (g/cm <sup>3</sup> ) (calculated by XRD)
Bulk Cu <sub>4</sub> TiSe <sub>4</sub>	5.6867	5.699
Nano-structured Cu <sub>4</sub> TiSe <sub>4</sub>	5.2728	5.702